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First Named Inventor:

Jaime Poris

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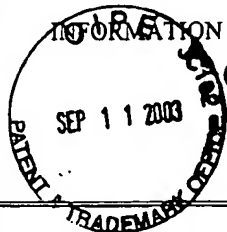
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Attorney Docket No.:

NAN042-1D US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)



U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
MR	26. 6,568,290	May 27, 2003	Poris	73	866	
MR	27. 2002/0174714A1	Nov. 28, 2002	McWaid et al.	73	105	
MR	28. 6,194,317	Feb 27, 2001	Kaisaki et al.	438	692	
MR	29. 4,512,661	Apr. 23, 1985	Claus et al.	356	351	
MR	30. 5,604,591	Feb. 18, 1997	Kitagawa	356	351	

Foreign Patent Documents

							Translation	
	Document	Date	Country	Class	Subclass		Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

MR	31.	Malacara, Daniel et al. "Interferogram Analysis For Optical Testing" 1998, Marcel Dekker, Inc. pp. 113
MR	32.	Stine, B. et al., "Rapid Characterization and Modeling of Pattern-Dependent Variation in Chemical-Mechanical Polishing", IEEE Transactions on Semiconductor Manufacturing, Vol. 11, No. 1, pp. 129-140 (Feb. 1998)

Examiner:

Date Considered

9-14-2004

*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.